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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/627,611	07/28/2003	Hiroshi Watanabe	402721	4283
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WASHINGTO	N, DC 20005-3960		2882	
			DATE MAILED: 06/19/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
Office Action Commence	10/627,611	WATANABE ET AL.				
Office Action Summary	Examiner	Art Unit				
	Chih-Cheng Glen Kao	2882				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period w  - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	TE OF THIS COMMUNICATION 6(a). In no event, however, may a reply be tim ill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 22 Ma	av 2006	•				
•						
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
·	A parto quayro, 1000 o.b. 11, 10					
Disposition of Claims						
4)⊠ Claim(s) <u>2-9 and 11-19</u> is/are pending in the application.						
4a) Of the above claim(s) is/are withdrawn from consideration.						
5)⊠ Claim(s) <u>2-8,11-13 and 19</u> is/are allowed.						
6)⊠ Claim(s) <u>9 and 14-18</u> is/are rejected.						
7) Claim(s) is/are objected to		·				
	election requirement	•				
8) Claim(s) are subject to restriction and/or election requirement.						
Application Papers		·				
9) The specification is objected to by the Examine	r .					
10)⊠ The drawing(s) filed on <u>17 November 2005</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
	• • • • • • • • • • • • • • • • • • • •					
11)☐ The oath or declaration is objected to by the Ex	aminer. Note the attached Office	Action or form PTO-152.				
Priority under 35 U.S.C. § 119		•				
12)⊠ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).						
a)⊠ All b)□ Some * c)□ None of:						
	1.⊠ Certified copies of the priority documents have been received.					
2. Certified copies of the priority documents have been received in Application No						
3. Copies of the certified copies of the priority documents have been received in this National Stage						
application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.						
		·				
Attachment(s)						
1) Notice of References Cited (PTO-892)  4) Interview Summary (PTO-413)  Paper No(s)/Mail Date						
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)  5) Notice of Informal Patent Application (PTO-152)						
Paper No(s)/Mail Date	6) Other:					

#### **DETAILED ACTION**

### Claim Objections

1. Claims 9 and 14-18 are objected to because of the following informalities, which appear to be minor draft errors including grammatical and/or lack of antecedent basis problems.

In the following format (location of objection; suggestion for correction), the following correction(s) may obviate the objection(s): (claim 9, line 8, "second-X-ray"; deleting the first hyphen), (claim 17, line 2, "said X-ray absorber"; replacing "said X-ray absorber" with - -at least one of said X-ray absorbers- -), and (claim 18, line 2, "said X-ray absorber"; replacing "said X-ray absorber" with - -at least one of said X-ray absorbers- -).

Claims 14-18 are objected to by virtue of their dependency. For purposes of examination, the claims have been treated as such. Appropriate correction is required.

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claim 9 is rejected under 35 U.S.C. 102(b) as being anticipated by Deguchi et al. (US 5414746).

Deguchi et al. discloses a method comprising forming an X-ray transmitter (fig. 22, #1), forming a first X-ray absorber (fig. 22, #12c) opposite said X-ray transmitter (fig. 22, #1), said

first X-ray absorber (fig. 22, #12c) including a plurality of spaced apart first X-ray absorber

portions, each first X-ray absorber portion having a first width (fig. 22, #12c), and forming a

second X-ray absorber (fig. 22, #12b), on said first X-ray absorber (fig. 22, #12c), said second X-

ray absorber (fig. 22, #12b) comprising a plurality of second X-ray absorber portions spaced

from each other (fig. 22, #12b), each second X-ray absorber portion (fig. 22, #12b) being

disposed on a corresponding one of the first X-ray absorber portions (fig. 22, #12c), each second

X-ray absorber portion having a second width (fig. 22, #12b), smaller than the first width (fig.

22, #12c).

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

- 3. Claims 14, 17, and 18 are rejected under 35 U.S.C. 103(a) as being unpatentable over Deguchi et al. as applied to claim 9 above, and further in view of Lee et al. (US 6534221).
- 4. Regarding claim 14, Deguchi et al. discloses a method as recited above. Deguchi et al. further discloses wherein tungsten (col. 17, lines 40-42) is employed as one of said first X-ray absorber and said second X-ray absorber.

However, Deguchi et al. fails to disclose diamond as an absorber.

Lee et al. teaches diamond as an absorber (col. 5, lines 8-9).

Application/Control Number: 10/627,611

Art Unit: 2882

It would have been obvious, to one having ordinary skill in the art at the time the invention was made, to include the method of Deguchi et al. with the diamond absorber of Lee et al., since one would be motivated to make such a modification for increasing the life of a device (col. 6, lines 29-31) as implied from Lee et al. Furthermore, it would have been obvious and within the general skill of a worker in the art to select a known material on the basis of its suitability.

- 5. Regarding claims 17 and 18, Lee et al. further teaches carbon as an absorber (col. 5, lines 8-9).
- 6. Claim 15 is rejected under 35 U.S.C. 103(a) as being unpatentable over Deguchi et al. as applied to claim 9 above, and further in view of Maehara et al. (US 5870448).

Deguchi et al. discloses a method as recited above.

However, Deguchi et al. fails to disclose forming an etching stopper film, stopping etching when etching a first X-ray absorber on an X-ray transmitter, and forming a second X-ray absorber on said etching stopper film.

Maehara et al. teaches forming an etching stopper film (fig. 1f, #104a), stopping etching when etching a first X-ray absorber (fig. 1f, #105b) on an X-ray transmitter (figs. 1a and 1f, #102), and forming a second X-ray absorber (fig. 1f, #106b) on said etching stopper film (fig. 1f, #104a).

It would have been obvious, to one having ordinary skill in the art at the time the invention was made, to include the method of Deguchi et al. with the etching stopping film of

Application/Control Number: 10/627,611

Art Unit: 2882

. Maehara et al., since one would be motivated to make such a modification for protecting the X-

ray transmitter (figs. 1A-1L) as implied from Maehara et al.

7. Claim 16 is rejected under 35 U.S.C. 103(a) as being unpatentable over Deguchi et al. as

applied to claim 9 above, and further in view of Sentoku et al. (US 5553110).

Deguchi et al. discloses a method as recited above.

However, Deguchi et al. fails to specifically disclose forming an interlayer film as an

etching stopper or a hard mask on a first X-ray absorber, and forming a second X-ray absorber

on said interlayer film.

Sentoku et al. teaches forming an interlayer film (fig. 13f, #164) as an etching stopper or

a hard mask on a first X-ray absorber (fig. 13f, #163), and forming a second X-ray absorber (fig.

13f, #165) on said interlayer film (fig. 13f, #164).

It would have been obvious, to one having ordinary skill in the art at the time the

invention was made, to include the method of Deguchi et al. with the interlayer film of Sentoku

et al., since one would be motivated to make such a modification for lowering noise (col. 21,

lines 13-15) as implied from Sentoku et al.

Allowable Subject Matter

8. Claims 2-8, 11-13, and 19 are allowed. The following is a statement of reasons for the

indication of allowable subject matter.

Page 5

Application/Control Number: 10/627,611

Art Unit: 2882

9. Regarding claim 7, prior art fails to disclose or fairly suggest a method including forming

Page 6

a laminated X-ray absorber on a surface of an X-ray transmitter, but not in recesses, wherein said

laminated X-ray absorber includes at least two layers having different compositions, wherein

phase shift of X-rays transmitted through said X-ray absorber is in a range of  $0.3\pi$  to  $0.6\pi$  and

transmittance of the X-rays transmitted through said X-ray absorber is in a range of 30% to 60%

for X-rays having an average exposure wavelength longer than 0.3 nm and shorter than 0.7 nm,

in combination with all the limitations in the claim. Claims 2-6, 8, and 19 are allowed by virtue

of their dependency.

10. Regarding claim 11, prior art fails to disclose or fairly suggest a method including

carrying out an exposure with an X-ray mask having a geometric X-ray phase difference between

a phase of X-rays transmitted through an X-ray transmission part of said X-ray mask and a phase

of X-rays transmitted through an X-ray absorber of said X-ray mask in a range including 0.5π

and in proximity to  $0.5\pi$ , wherein a laminated structure includes at least two layers having

different compositions, and either a phase shift of the X-rays transmitted through said X-ray

absorber is in a range of  $0.3\pi$  to  $0.6\pi$  or the transmittance of the X-rays transmitted through said

X-ray absorber is in a range of 30% to 60%, in combination with all the limitations in the claim.

Claims 12 and 13 are allowed by virtue of their dependency.

Response to Arguments

11. Applicant's arguments with respect to claims 9 and 14-18 have been considered but are

moot in view of the new ground(s) of rejection.

Art Unit: 2882

#### Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Chih-Cheng Glen Kao whose telephone number is (571) 272-2492. The examiner can normally be reached on M - F (9 am to 5 pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Ed Glick can be reached on (571) 272-2490. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Art Unit: 2882

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

gk

EDWARD J. GLICK SUPERVISORY PATENT EXAMINER